



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Yuanning Chen, et al.

Serial No.: 10/719,280

Filed: 11/21/03

For: Use of Hafnium Silicon Oxynitride as the Cap Layer of the Sidewall Spacer

TI-35022.1

Examiner: TBD

Art Unit: TBD

**LETTER TO THE OFFICIAL DRAFTSPERSON**

**MAILING CERTIFICATE UNDER 37 C.F.R. §1.8(A)**

I hereby certify that the above correspondence is being deposited with the U.S. Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

*Karen Vertz*  
Karen Vertz

*12-8-03*  
Date

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

Enclosed is **ONE (1)** sheet of formal drawings for the above-referenced case. Please charge any necessary fees to Deposit Account No. 20-0668 of Texas Instruments Incorporated. This sheet is enclosed in triplicate.

Respectfully submitted,

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